

Abstract of the Disclosure

A method of growing a thin film onto a substrate. A precursor of the film is fed into a reaction space in the form of a vapor phase pulse causing the precursor to  
5 adsorb onto the surface of the substrate to form a layer thereof. A catalyst is subsequently fed into the reaction space in an amount to substantially convert the layer of the precursor to the desired thin film. The above steps may be repeated to achieve the desired film thickness.

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